IPW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: 2813 Examiner: Heather Doty Confirmation No.: 2155

In Re	PAT	ENT	APPI	JICA	T	ION	of
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Applicant(s):	HIROTAKA KUMATSUBARA	
Serial No.:	10/765,156	,
Filing Date:	January 28, 2004	AMENDMENT
For:	METHOD FOR MANUFACTURING SOI LOCOS MOSFET WITH METAL OXIDE	UNDER
	FILM OR IMPURITY-IMPLANTED FIELD OXIDE (as amended)	RULE 312
Atty. Docket:	(KAN 155)	

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Please enter the attached Replacement Sheet to correct the inadvertent submission of an explanatory sketch as a drawing change, in the last amendment. The attached sheet merely reinstates the original drawing sheet that was already approved, and removes the error of the last amendment. The Applicant regrets any inconvenience to the PTO.

Respectfully submitted,

August 16, 2005

Date

Nick Bromer (Reg. No. 33,478)

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